Mega-Etch Filter

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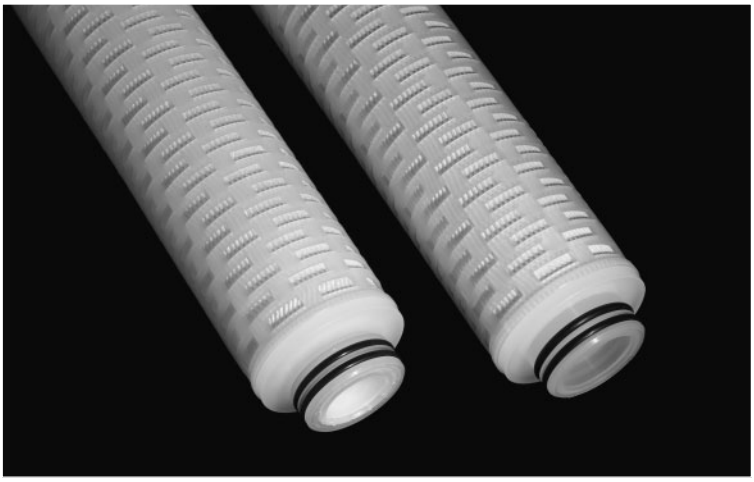


Description

The Mega-Etch filter is targeted for use in recirculating etch baths. Utilizing our patented asymmetric polysulfone membrane enables the Mega-Etch filter to provide the following benefits:

- Available in retention ratings of 0.05, 0.1, 0.2, 0.45 µm
- High flow vs. low-pressure drop
- No pre-wetting with IPA required
- Fast bath clean-up •
  Patented highly asymmetric polysulfone membrane assures long life

Specifications

Materials

- Medium: Highly asymmetric hydrophilic polysulfone
- Hardware: Polypropylene
- Support: Polypropylene
- O-ring: Viton[1] A (standard)

Removal Ratings

- 0.45 µm (0.1 µm RP[2]), 0.2 µm, 0.1 µm, 0.05 µm

Filter Areas

- 10" / 254 mm - 7.0 ft.^{2} / 0.65 m^2
- 20" / 508 mm - 14.0 ft.^{2} / 1.30 m^2

Configurations

- Nominal Length:
  10" / 25.4 cm, 20" / 50.8 cm
- Diameter 2.6" / 6.6 cm

Operating Conditions

Maximum Operating Temperature:

- 203˚F / 95˚C

Maximum Forward Differential Pressure:

- 50 psid @ 60˚F / 3.45 bar @ 20˚C

Performance Parameters

Mega-Etch cartridges are available in single pass ratings of 0.05, 0.1, 0.2, or 0.45 µm. In addition, the Mega-Etch 0.45 (EBC450) cartridge has a Recirculating Performance of 0.1 µm[2].

Target Applications

The Mega-Etch cartridge is used as the primary filter in recirculating etch baths. When operated at ambient temperature, it is compatible with a wide variety of etch solutions.[2]

The Mega-Etch cartridge is highly recommended for use in SiO_2 Etch with surfactant and low horsepower internal pumps.

The Mega-Etch cartridge will pressure wet when used in SiO_2 Etch without surfactant and with higher horsepower pumps, or use the Pall Ulti-Etch™ Filter for spontaneous wetting in high surface tension fluids.

The Mega-Etch cartridge is recommended for use in semi-aqueous strippers that are primarily HF based.[2]

[1] Viton is a trademark of DuPont Dow Elastomers
[2] Recirculating Performance. See Technical Bulletin 1038-T for more information.
[3] Before installation, the Mega-Etch cartridge should be tested to determine compatibility

Part Numbers / Ordering Information

EBC ■ ● ◆ ▲

EBC Etch BathCartridge

Code ■	Removal Ratings in Microns (µm)
050	0.05
100	0.1
200	0.2
450	0.45 (0.1 RP[2])

Code ●	Cartridge Lengths
10	10" / 254 mm
20	20" / 508 mm

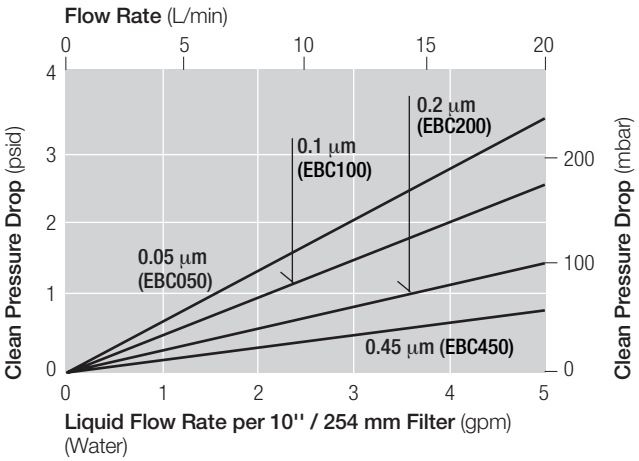
Code ◆	End Configurations
M3	SOE flat closed end, external 222 O-rings
M7	SOE fin end, external 226 O-rings
M8	SOE fin end, external 222 O-rings

Code ▲	O-Ring Materials
V	Viton A (standard)
T	FEP Encapsulated Silicone
F	FEP Encapsulated Viton A
C	Chemraz[4]

[4] Chemraz is a trademark of Greene, Tweed & Co.

Unit conversion: 1 bar = 100 kilopascals

Pressure Drop vs. Liquid Flow Rate[5]



[5] For liquids with viscosity differing from water, multiply the pressure drop by the viscosity in centipoise.

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